

ABSTRACT

SUBSTRATE CLEANING MEMBER AND SUBSTRATE CLEANING APPARATUS

Provided is a substrate cleaning apparatus including: a substrate support mechanism configured to support a substrate; and a roll-type first cleaning member configured to clean a first surface of the substrate by rotating while being in contact with a bevel and/or an edge of the first surface of the substrate, wherein a rotation axis of the first cleaning member is in parallel with the substrate, and the first cleaning member has a large diameter portion and a small diameter portion.

Figure 5